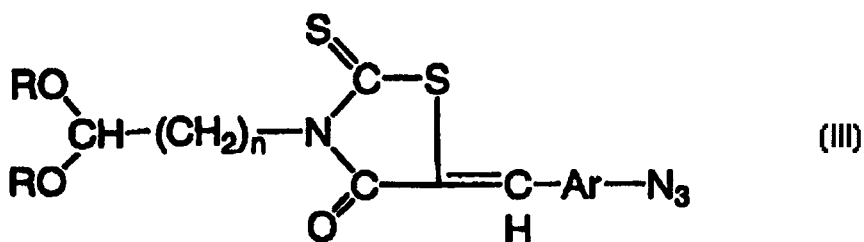
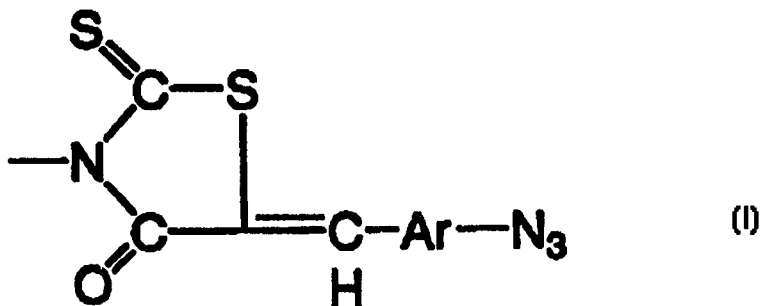




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(54) Title: PHOTSENSITIVE COMPOUNDS, PHOTSENSITIVE RESIN COMPOSITIONS, AND PATTERN FORMATION METHOD MAKING USE OF THE COMPOUNDS OR COMPOSITIONS

**(57) Abstract**

The photosensitive compound of the present invention contains the unit (I) and is particularly expressed by the following formula (III). Different photosensitive resin compositions can be prepared from this novel photosensitive resin compound, and the thus-obtained photosensitive resin compositions do not raise the problem of environmental pollution, are endowed with high resolution, possess a high level of sensitivity, and exhibit excellent adhesion with substrates, coating characteristics, and storage stability.

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